

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	5657	photomask with materials	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:29
L2	3	photomask with materials same sealant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 10:49
L3	278	(pores pore) and seal\$4 and via	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 10:52
L4	30	(pores pore) and seal\$4 and via with hole	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 10:50
L5	2452	(257/774).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/28 10:52
L6	0	5 and (pores pore) and seal\$4	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 10:53
L7	19	5 and (pores pore) and seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 10:59
L8	7	5 and (pores pore) with seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 10:53
L9	6	("5243222" "6229211" "6677678").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 10:59
L10	12	("4659205" "5477057" "5550007" "5824599" "5882999" "5906911" "5910453" "5933761" "6121156" "6225217" "6323076" "6355555").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/28 11:00

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L11	16	("3622382" "4465705" "4789648" "4925805" "4968636" "5091763" "5314843" "5316965" "5324680" "5429955" "5578523" "5672531" "5677224" "5712185" "5741626" "5796133").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/28 11:10
L12	0	"64445557".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/28 11:10
L13	2	"6444557".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 11:10
L20	2	"20050127515".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:43
L21	291	dielectric with constant with (silica adj aerogel MSQ)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:07
L22	2	"5741626".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:15
L23	5	photoresist with (photosensitive near1 polyimide BCB)same (silsequioxane MSQ silica near1 aerogel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:19
L24	632	photoresist with (photosensitive near1 polyimide BCB)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:20
L25	4	photoresist with (photosensitive near1 polyimide and BCB)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:24

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L26	2	photoresist with spin with coating with MSQ	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:24
L27	0	(photo near1 resist photo near1 mask) with spin with coating with MSQ	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:25
L28	2	(photo\$2resist photo\$2mask) with spin with coating with MSQ	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:25
L29	8	photomask with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:29
L30	323271	photoresist wit made with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:29
L31	0	photoresist with made with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:30
L32	26	photoresist with made with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:30
L33	0	"photoresit" near2 made	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:43
L34	16	photoresit with material	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:44

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L35	0	photoresit with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:45
L36	0	photoresit with orgnic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:45
L37	9	photoresit with organic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:45
L38	0	photoresit with photosensitive adj polyimide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:46
L39	0	photoresit with photosensitive adj polyimide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:46
L40	442	resist with photosensitive adj polyimide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:46
L41	37	resist with (BCB photosensitive adj polyimide) and damascene	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:50
L42	56	resist with (BCB photosensitive adj polyimide) and interconnect and "257"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 15:51

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L43	28	(US-20050173804-\$ or US-20010051420-\$ or US-20030143839-\$ or US-20030001282-\$ or US-20020055256-\$ or US-20050048765-\$ or US-20030134508-\$ or US-20010054769-\$ or US-20050133920-\$ or US-20050127515-\$ or US-20050003594-\$ or US-20040256618-\$ or US-20020182851-\$ or US-20020016070-\$).did. or (US-6903006-\$ or US-4832788-\$ or US-5759911-\$ or US-6541842-\$ or US-6586334-\$ or US-6528409-\$ or US-6482733-\$ or US-6180518-\$ or US-4661697-\$ or US-5741626-\$ or US-6486057-\$ or US-6593220-\$). did. or (DE-10014587-\$).did. or (JP-04158557-\$).did.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2006/02/28 20:04
L44	1	43 and soak\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 20:05
S1	12	("6482733" "6518168" "6528409" "6585811" "6586334" "6689686").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 16:50
S2	2	"20050127515".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 17:56
S3	2679	(257/e21.576).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/27 18:11
S4	0	S1 and sidewall with photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 18:58

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S5	6	S3 and sidewall with photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 18:00
S6	36	S3 and sidewall with treatment	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 18:01
S7	9	S3 and sidewall with prevent with copper	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 18:02
S8	25	S3 and sidewall with prevent\$3 with copper	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 18:08
S9	0	S3 and sidewall with liner with (benzocyclobutane BCB photosensitive polyimide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 20:18
S10	2	S3 and sidewall with barrier with (benzocyclobutane BCB photosensitive polyimide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 18:11
S11	0	S3 and sidewall with prevent\$3 with (benzocyclobutane BCB photosensitive polyimide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 18:46
S12	9202	(257/e21.57\$1).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/27 18:11
S13	36	S12 and sidewall with (barrier cap\$3 lin\$3 coat\$3 film layer prevent\$3) with (benzocyclobutane BCB photosensitive polyimide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 20:10

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S14	36	S13 not S8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 18:13
S15	6	("5141817" "5955528" "5962113" "6162838" "6319854" "6380346").PN. OR ("6903006"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 18:26
S16	35	("4789648" "4837123" "4921723" "5081060" "5100838" "5106780" "5118382" "5144411" "5286674" "5525552" "5663101").PN. OR ("5759911").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 18:38
S17	4	S3 and sidewall with photomask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 18:46
S19	20	S12 and sidewall with porous with surface	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 19:02
S20	21	("20010051420" "20020055256" "20 030001282" "20030143839" "61805 18" "6482733" "6518166" "6528409" "6585811" "6586334" "6689686"). PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 19:17
S21	2	"6541842".PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 19:17
S22	3	("5103285" "5818071" "6231989").PN. OR ("6541842"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:37
S23	1	("2002/0055256").URPN.	USPAT	OR	ON	2006/02/27 19:41
S24	1	"6586334".pn.	USPAT	OR	ON	2006/02/27 19:41
S25	6	("20010019884" "6217721" "6319822" "6326297" "6380628"). PN. OR ("6586334").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:41
S26	44	S12 and pore near2 seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 20:12

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S27	64	S12 and (pores porous) near2 seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 20:12
S28	87	(pores porous) near2 seal\$4 same (benzocyclobutane BCB photosensitive polyimide photo near2 resist photo near2 mask)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 20:34
S29	1229	(257/762).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/28 10:52
S30	1	S29 and (pores porous) near2 seal\$4 and (benzocyclobutane BCB photosensitive polyimide photo near2 resist photo near2 mask)with (seal\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 20:35
S31	12	S29 and (pores porous) near2 seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 20:44
S32	494	(257/767).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/27 20:44
S33	2	S32 and (pores porous) near2 seal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 20:51
S34	2	"5412868".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 20:56
S35	12	("6482733" "6518168" "6528409" "6585811" "6586334" "6689686").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:04

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S36	840	silicon near2 oxide with photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:04
S37	0	silicon near2 oxide with photosensitive same pore with (seal\$5)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:05
S38	23	silicon near2 oxide with photosensitive with polyimide with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:22
S39	186480	silicon near2 oxide (photomask photoresist photosensitive polyimide BCB)with selant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:09
S40	0	silicon near2 oxide with (photomask photoresist photosensitive polyimide BCB)with selant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:09
S41	0	silicon near2 oxide with (photomask photoresist photosensitive polyimide BCB) with selant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:09
S42	39	silicon near2 oxide with (photomask photoresist photosensitive polyimide BCB) with seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:12
S43	97	(silicon near2 oxide "SiO.sub.2")with (photomask photoresist photosensitive polyimide BCB) with seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:13
S44	58	S43 not S42	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:13

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S45	12	(silicon near2 oxide "SiO.sub.2")with (photomask photoresist photosensitive polyimide BCB) near4 seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:22
S46	1568	(photomask photoresist photosensitive BCB) near4 seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:15
S47	9	(photomask photoresist photosensitive BCB) near4 seal\$3 and (pores porous) with via	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:15
S48	1087	(silicon near2 oxide "SiO.sub.2")with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:17
S49	2	(silicon near2 oxide "SiO.sub.2")with BCB with seal\$5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:17
S50	27	("siO.sub.2" silicon near2 oxide) with photosensitive with polyimide with BCB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:27
S51	1	benzocyclobutene near2 sealant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:28
S52	3	benzocyclobutene near2 seal\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 21:28
S53	17	benzocyclobutene near2 low with k	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/28 10:28